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★ NWCO S02 93-218705/27 ★ SU 1747877-A1
Interference measurement of thickness of semi-conducting layers.
includes direction of monochromatic light at various angles onto
sample and plotting of angular dependency of reflected light
intensity

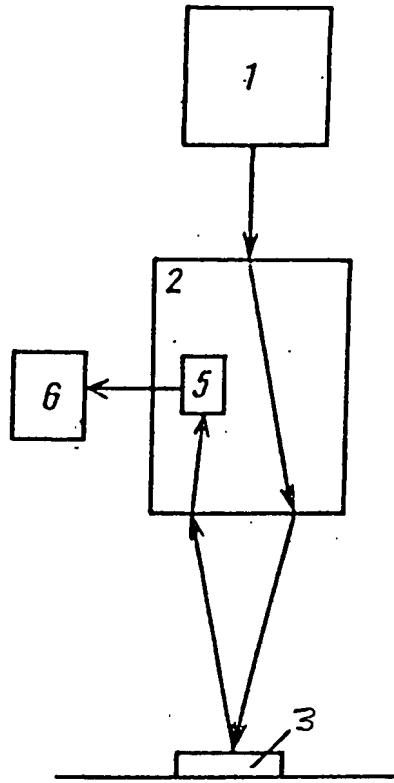
NW CORRESPONDENCE POLY 90.02.28 90SU-4796932
(92.07.15) G01B 11/06

A monochromatic light is directed from a source through a beam directing unit onto a test sample (3) and a ray reflected from the sample is passed through the directing unit to a photoreceiver (5), passing a signal to a recorder (6). The angle of incidence is changed, to obtain the angular dependency of reflected light intensity and the result is calculated in terms of the distance between extrema of the function.

USE/ADVANTAGE - For determin of thickness of semiconductor films. Improved efficiency is claimed. Bul.26/15.7.92 (5pp
Dwg.No.4/4)

N93-167577

S02-A03B1



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